

Docket No.: M4 .0319/P319

Appro.: 09/296,835 Docket No.: Inventor: Ronald A. Weimer, et al. Title: FABRICATION OF DRAM AND OTHER

SEMICONDUCTOR DEVICES WITH AN INSULATING FILM USING A WET RAPID THERMAL OXIDATION PROCESS

Sheet 1 of 7

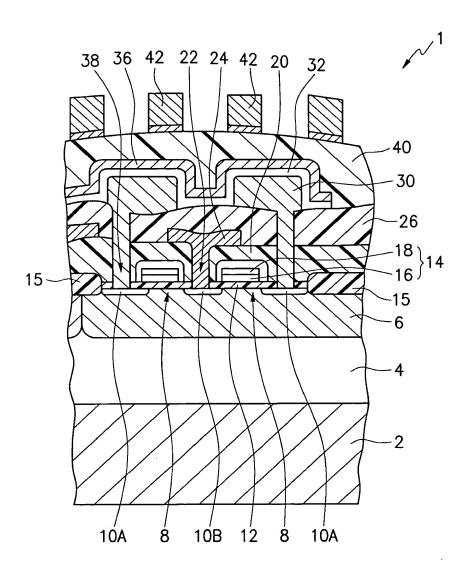


FIG. 1



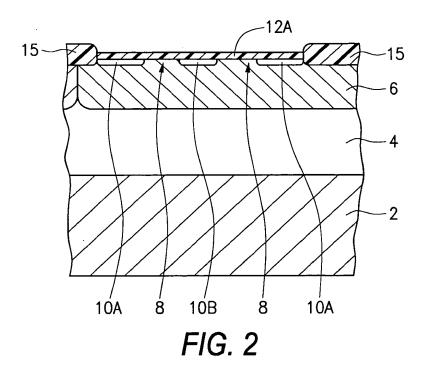
App No.: 09/296,835

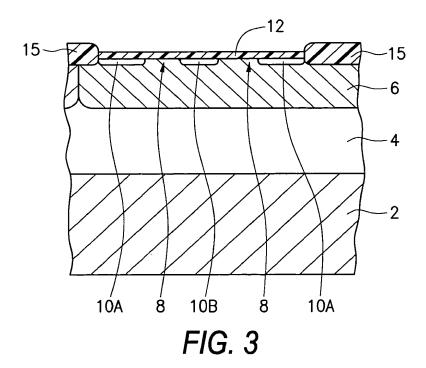
Docket No.: M406 19/P319

Inventor: Ronald A. Weimer, et al.

Title: FABRICATION OF DRAM AND OTHER SEMICONDUCTOR DEVICES WITH AN INSULATING FILM USING A WET RAPID THERMAL OXIDATION PROCESS

Sheet 2 of 7



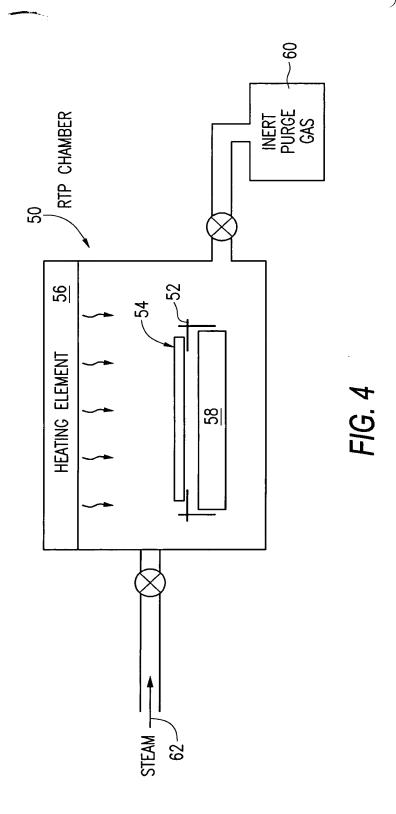




App No.: 09/296,835 Docket No.: M406 19/P31 Inventor: Ronald A. Weimer, et al.
Title: FABRICATION OF DRAM AND OTHER SEMICONDUCTOR DEVICES WITH AN INSULATING FILM USING A WET RAPID THERMAL OXIDATION PROCESS

Sheet 3 of 7

Docket No.: M406 19/P319





Docket No.: M4065.0319/P319

App No.: 09/296,835 Docket No.: M4065.0319/P31
Inventor: Ronald A. Weimer, et al.
Title: FABRICATION OF DRAM AND OTHER
SEMICONDUCTOR DEVICES WITH AN INSULATING FILM
USING A WET RAPID THERMAL OXIDATION PROCESS

Sheet 4 of 7

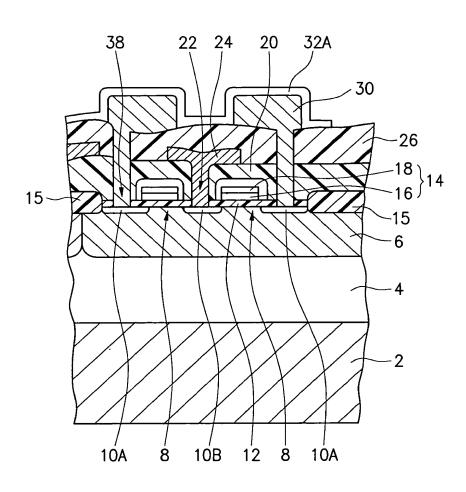


FIG. 5



Docket No.: M4065.0319/P319

App No.: 09/296,835 Inventor: Ronald A. Weimer, et al.

Title: FABRICATION OF DRAM AND OTHER
SEMICONDUCTOR DEVICES WITH AN INSULATING FILM
USING A WET RAPID THERMAL OXIDATION PROCESS

Sheet 5 of 7

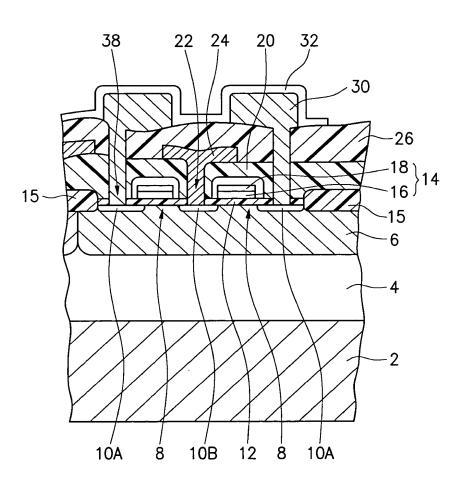


FIG. 6



App No.: 09/296,835 Docket No.: M4065.0319/P319

Inventor: Ronald A. Weimer, et al.

Title: FABRICATION OF DRAM AND OTHER

SEMICONDUCTOR DEVICES WITH AN INSULATING FILM USING A WET RAPID THERMAL OXIDATION PROCESS

Sheet 6 of 7

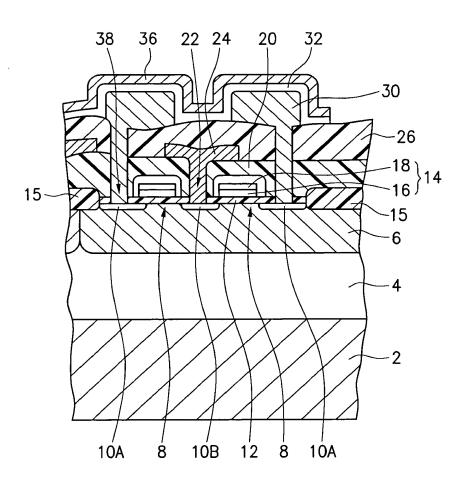


FIG. 7



App No.: 09/296,835

Docket No.: M4065.0319/P319

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SEMICONDUCTOR DEVICES WITH AN INSULATING FILM USING A WET RAPID THERMAL OXIDATION PROCESS

Sheet 7 of 7



SUBJECT THE INSULATING FILM TO A HEAT TREATMENT IN AN AMBIENT COMPRISING A STABILIZING GAS INCLUDING A GAS SELECTED FROM THE GROUP CONSISTING OF  $N_2$ ,  $O_2$ ,  $O_3$ , NO, or  $N_2O$ 

SUBJECT THE INSULATING FILM TO A WET OXIDATION IN A RAPID THERMAL PROCESS (RTP) CHAMBER

FIG. 8